AMENDMENT UNDER 37 C.F.R. § 1.111 Attorney Docket No.: Q96031

U.S. Appln. No.: 10/588,735

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the

application:

LISTING OF CLAIMS:

1-15. (canceled).

16. (currently amended): A photocatalyst material producing method characterized by

comprising

forming a discharge zone with a discharge gap part defined therein by first and second

electrodes facing each other and arranging a dielectric material on a surface of the first

electrode facing to the second electrode,

coating the second electrode or the surface of the dielectric material with a metal or

metal compound to be a photocatalyst material,

supplying oxygen gas containing ozone into the discharge gap part, applying an AC

voltage between the first electrode and the second electrode to introduce AC power of a

predetermined power density into the discharge zone, causing dielectric barrier discharge (

silent discharge or creeping discharge) via the dielectric material, creating a state where oxygen

gas and ozone gas exist in the discharge gap part,

modifying the surface of the dielectric material or the surface of the second electrode

contacting the discharge gap part to an oxidized surface by a mutual chemical reaction of high-

field intermittent discharge plasma due to the dielectric barrier discharge (silent discharge or

creeping discharge) and oxygen gas and ozone gas, thus adhering a photocatalyst material to

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or photocatalyst material.

the surface of the dielectric material or the metal surface of the second electrode, and taking outremoving the surface of the dielectric material or the surface of the second

electrode, and using it as a photocatalyst material surface or photocatalyst material.

17. (currently amended): The photocatalyst material producing method as claimed in claim 16, characterized in that gas pressure in the discharge gap part or AC power injected into the discharge zone is varied in accordance with an element material to be a photocatalyst material coating the second electrode or the surface of the dielectric material, thereby controlling a predetermined power density, and taking outremoving the surface of the dielectric material or the surface of the second electrode, and using it as a photocatalyst material surface

18. (currently amended): The photocatalyst material producing method as claimed in

claim 16, characterized in that the metal or metal compound to be the photocatalyst contains

one or more elements of CUCu, In, Zn, Fe, Cr, Pb, V, W, Bi, Nb and Sr.

19. (currently amended): A photocatalyst material producing method characterized by comprising

forming a discharge zone with a discharge gap part defined therein by first and second electrodes facing each other and arranging a dielectric material on a surface of the first electrode facing to the second electrode,

supplying <u>a</u>staring material gas containing metal <u>Particles particles</u> or <u>a</u> metal

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compound gas to be a photocatalyst element <u>contained</u> in <u>an</u> oxygen gas to the discharge gap part, applying an AC voltage between the first electrode and the second electrode to introduce AC power of a predetermined power density into the discharge zone, causing dielectric barrier discharge (<u>silent discharge or creeping discharge</u>) via the dielectric material, creating a state where oxygen gas and ozone gas exist in the discharge gap part, and

modifying the metal particles or the metal compound gas contained in the oxygen gas to photocatalyst particles by a mutual chemical reaction of high-field intermittent discharge plasma due to the dielectric barrier discharge (silent discharge or creeping discharge) and oxygen gas and ozone gas.

- 20. (previously presented): The photocatalyst material producing method as claimed in claim 19, characterized in that gas pressure in the discharge gap part or AC power injected into the discharge zone is varied in accordance with metal particle or metal compound gas type to be a photocatalyst element contained in the starting material gas, thereby controlling a predetermined power density.
- 21. (currently amended): The photocatalyst material producing method as claimed in claim 19, characterized in that the metal particle or metal compound gas contains one or more elements of CUCu, In, Zn, Fe, Cr, Pb, V, W, Bi, Nb and Sr.
- 22. (previously presented): The photocatalyst material producing method as claimed in claim 16, characterized in that the purity of the oxygen gas is 99.99% or higher.

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23. (previously presented): The photocatalyst material producing method as claimed in

claim 19, characterized in that the purity of the oxygen gas is 99.99% or higher.

24. (previously presented): The photocatalyst material producing method as claimed

in claim 16, characterized in that a product value of a gap length dg of the discharge

gap part and a gas pressure P is defined as (P+0.1)*dg value, and the (P+0.1)*dg value is

0.14 (MPa*mm) or less.

25. (previously presented): The photocatalyst material producing method as claimed is

claim 19, characterized in that a product value of a gap length dg of the discharge gap part and

a gas pressure P is defined as (P+0.1)*dg value, and the (P+0.1)*dg value is 0.14 (MPa*mm)

or less.

26. (previously presented): The photocatalyst material producing method as claimed in

claim 16, characterized in that the frequency of an AC power source that injecting AC power of

the predetermined power density is set at a predetermined frequency or lower, or at 30 kHz or

lower.

27. (previously presented): The photocatalyst material producing method as claimed in

claim 19, characterized in that the frequency of an AC power source that injecting AC power of

the predetermined power density is set at a predetermined frequency or lower, or at 30 kHz or

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lower.

28. (previously presented): The photocatalyst material producing method as claimed in claim 16, characterized in that dilute gas to be auxiliary starting material gas is contained in the oxygen gas to enhance photocatalyst material production efficiency.

29. (previously presented): The photocatalyst material producing method as claimed in claim 19, characterized in that dilute gas to be auxiliary starting material gas is contained in the oxygen gas to enhance photocatalyst material production efficiency.

30. (currently amended): The photocatalyst material producing method as claimed in claim 16, characterized in that electrode cells, each including the first electrode, second electrode and dielectric material, are stacked in multiple stages or the area of the electrodes is increased to increase injected AC power, thus enabling simultaneous production of a large quantity of photocatalyst material particles, a large-photocatalyst surface, and a plurality of photocatalyst plates.

31. (currently amended): The photocatalyst material producing method as claimed in claim 19, characterized in that electrode cells, each including the first electrode, second electrode and dielectric

material, are stacked in multiple stages or the area of the electrodes is increased to increase injected AC cower, thus enabling simultaneous production of a large-quantity of

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photocatalyst material particles, a large-photocatalyst surface, and a plurality of photocatalyst

plates.

32. (previously presented): The photocatalyst material producing method as claimed in

claim 16, characterized in that nitrogen gas is contained in the oxygen gas and a photocatalyst

material containing nitrogen is produced.

33. (previously presented): The photocatalyst material producing method as claimed in

claim 19, characterized in that nitrogen gas is contained in the oxygen gas and a photocatalyst

material containing nitrogen is produced.

34. (currently amended): The photocatalyst material producing method as claimed in

claim 16, characterized in that wherein the oxygen gas supplied to the discharge gap part is an

ozonized oxygen gas containing ozone is supplied by an ozonizer that provided on a previous

stage.

35. (currently amended): The photocatalyst material producing method as claimed in

claim 19, characterized in thatwherein the oxygen gas supplied to the discharge gap part is an

ozonized oxygen gas containing ozone is supplied by an ozonizer-that provided on a previous

stage.

36. (currently amended): A photocatalyst material producing apparatus characterized by

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comprising:

a photocatalyst material producing unit housing a first electrode, a second electrode facing this first electrode to form a discharge zone with a discharge gap part defined therein, and a dielectric material arranged on a surface of the first electrode facing to the second electrode;

oxygen supply means that supplies oxygen gas into the discharge gap part in the photocatalyst material producing unit; and

an AC power source that applies an AC voltage between[[.]] the first electrode and the second electrode to introduce AC power of a predetermined power density into the discharge zone and causes dielectric barrier discharge (silent discharge or creeping discharge) via the dielectric material;

wherein a metal or metal compound to be a photocatalyst material is applied to the second electrode or the surface of the dielectric material,

a state where oxygen gas and ozone gas exist in the discharge gap part is created by the dielectric barrier discharge, and

the surface of the dielectric material or the surface of the second electrode contacting the discharge gap part is modified to an oxidized surface by a mutual chemical reaction of high-field intermittent discharge plasma due to the dielectric barrier discharge (silent discharge or creeping discharge) and oxygen gas and ozone gas, thus adhering a photocatalyst material to the surface of the dielectric material or the metal surface of the second electrode.

37. (currently amended): A photocatalyst material producing apparatus characterized by

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comprising:

a photocatalyst material producing unit housing a first electrode, a second electrode facing this first electrode to form a discharge zone with a discharge gap part defined therein, and a dielectric material arranged on a surface of the first electrode facing to the second electrode;

starting material gas supply means that supplies starting material gas containing metal particles or metal compound gas to be a photocatalyst element in oxygen gas to the discharge gap part in the photocatalyst material producing unit;

an ozonizer; and

an AC power source that applies an AC voltage between the first electrode and the second electrode to introduce AC power of a predetermined power density into the discharge zone and causes dielectric barrier discharge (silent discharge or creeping discharge) via the dielectric material;

wherein a state where oxygen gas and ozone gas exist in the discharge gap part is created by the dielectric barrier discharge (silent discharge or creeping discharge), and

the metal particles or the metal compound gas contained in the oxygen gas is modified to photocatalyst particles by a mutual chemical reaction of high-field intermittent discharge, plasma due to the dielectric barrier discharge (silent discharge or creeping discharge) and oxygen gas and ozone gas.

38. (new): The photocatalyst material producing method as claimed in claim 16, wherein the dielectric barrier discharge is a silent discharge or a creeping discharge.

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39. (new): The photocatalyst material producing method as claimed in claim 19, wherein the dielectric barrier discharge is a silent discharge or a creeping discharge.

40. (new): The photocatalyst material producing apparatus as claimed in claim 36, wherein the dielectric barrier discharge is a silent discharge or a creeping discharge.

41. (new): The photocatalyst material producing apparatus as claimed in claim 37, wherein the dielectric barrier discharge is a silent discharge or a creeping discharge.